

## REACTION FORCE ISOLATION SYSTEM

### ABSTRACT OF THE DISCLOSURE

An exposure apparatus comprising an optical system for imaging a pattern formed in a reticle onto an article and a reticle stage for supporting the article. A motor is provided for positioning the reticle stage and reticle relative to the optical system and includes a first motor portion and a second motor portion. The first motor portion is connected to the reticle stage and movable relative to the second motor portion. The apparatus further comprises a vibration isolation device configured to isolate vibration resulting from reaction forces created between the first and second motor portions. A method of directing reaction forces created between the first and second motor portions is also disclosed.